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**INFORMATION DISCLOSURE STATEMENT**

(Use several sheets if necessary)

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Group: 2811

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
Loke	5,147,826	09/15/92	Liu et al			
	5,275,851	01/04/94	Fonash et al			
	5,134,018	07/28/92	Tokunaga			
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	5,920,781	07/06/99	Imoto			
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	5,830,787	11/03/98	Kim			
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✓	5,946,561	08/31/99	Yamazaki et al			
Loke	5,091,334	02/25/92	Yamazaki et al			

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date	Country	Class	Subclass	Translation Yes No
Loke	EP 0 474 289 A1	03/11/92	Europe			
	63-258063	10/25/88	Japan			Abstract
✓	62-188373	08/17/87	Japan			Abstract
Loke	5-21763	01/29/93	Japan			Abstract

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

Loke	Hempel et al., "Needle-Like Crystallization of Ni Doped Amorphous Silicon Thin Films", Solid State Communications, Vol. 85, No. 11, March 1993, pp. 921-924
	Hayzelden et al., "In Situ Transmission Electron Microscopy Studies of Silicide-Mediated Crystallization of Amorphous Silicon", Appl. Phys. Lett., Vol. 60, No. 2, January 13, 1992, pp. 225-227
	Dvurenchenskii et al., "Transport Phenomena in Amorphous Silicon Doped by Ion Implantation of 3d Metals", Phys. Stat. Sol. Vol. (a) 95, (1986), pp. 635-640
	Crowder et al., "DMOS FET with Common Field and Channel Doping", IBM Technical Disclosure Bulletin, Vol. 20, No. 4, September 1977, pp. 1617-1621
✓	Fathimulla et al., "Reactively rf Magnetron Sputtered AlN Films as Gate Dielectric", J. Appl. Phys., Vol. 54, No. 8, August 1983, pp. 4586-4589
Loke	Gerova, "Deposition of AlN Thin Films by Magnetron Reactive Sputtering", Thin Solid Films - Preparation and Characterization, Vol. 81, (1981), pp. 201-205

Examiner

Loke

Date Considered

9/28/00

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



